

EI-27003: Electronics Devices and Circuits

Lecture - 14

Subject Incharge: Mr. Rajesh Khatri
Associate Professor

LECTURE - 14

Year: 2020-21

Numerical

- Consider a process technology for which $L_{\min}=0.4\mu\text{m}$, $t_{\text{ox}}=8\text{nm}$, $\mu_n=450\text{cm}^2/\text{v}\cdot\text{s}$ and $V_t=0.7\text{V}$.
- (a) Find C_{ox} and K_n
- (b) For a MOSFET with $W/L=8\mu\text{m}/0.8\mu\text{m}$, calculate the values of V_{GS} and V_{DSmin} needed to operate the transistor in the saturation region with dc current $I_D=100\mu\text{A}$.
- (c) For the device in (b), find the value of V_{GS} required to cause the device to operate as a 1000Ω resistor for very small V_{DS} .

- Solution: (a) $C_{\text{ox}} = \frac{\epsilon_{\text{ox}}}{t_{\text{ox}}} = \frac{3.45 \times 10^{-11}}{8 \times 10^{-9}} = 4.32 \times 10^{-3} \text{ F/m}^2 = 4.32 \text{ fF}/\mu\text{m}^2$

$$K_n = \mu_n C_{\text{ox}} = 450 \times 4.32 = 194 \mu\text{A}/\text{V}^2$$

- For MOS operation in saturation region:

$$I_D = \frac{1}{2} K_n \frac{W}{L} (V_{\text{GS}} - V_t)^2$$

Numerical

- $100 = \frac{1}{2} \times 194 \times \frac{8}{0.8} (V_{GS} - 0.7)^2$
 - $V_{GS} - 0.7 = 0.32V$
 - OR $V_{GS} = 1.02V$
- Hence $V_{DSmin} = V_{GS} - V_t = 0.32V$

- For MOSFET in triode region with V_{DS} very small

$$I_D = K_n \frac{W}{L} (V_{GS} - V_t) V_{DS}$$

From which the drain to source resistance r_{DS} can be written as:

$$r_{DS} = \frac{V_{DS}}{I_D} \Bigg\} \text{small } V_{DS}$$

$$= 1/K_n \frac{W}{L} (V_{GS} - V_t)$$

$$1000 = \frac{1}{194 \times 10^{-6} \times 10 (V_{GS} - 0.7)}$$

Numerical

- This gives $V_{GS} - 0.7 = 0.52V$
- OR

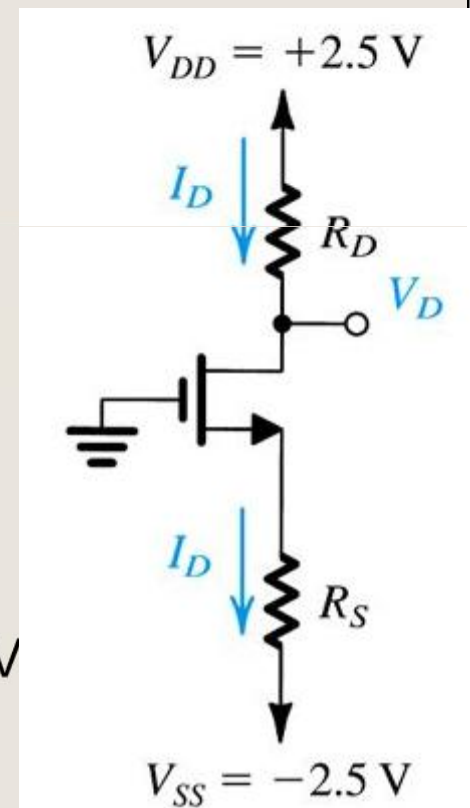
$$V_{GS} = 1.22V$$

Numerical -2

- Design the circuit shown in fig, so that the transistor operates at $I_D=0.4\text{mA}$ and $V_D=+0.5\text{V}$. The NMOS transistor has $V_t=0.7\text{V}$, $\mu_n C_{ox}=100\mu\text{A/V}^2$, $L=1\mu\text{m}$ and $W=32\mu\text{m}$. Neglect the channel-length modulation effect.

Solution

- Since $V_D=+0.5\text{V}$, $V_G=0\text{V}$
- $V_{DS}<(V_{GS}-V_t)$ triode region & $V_{DS}>(V_{GS}-V_t)$ sat. region
- $V_D>V_G$, it means that NMOS is operating in saturation region. So use saturation equation to find V_{GS} .
- $$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_t)^2$$
- $$400 = \frac{1}{2} 100 \frac{32}{1} (V_{GS} - V_t)^2$$
- Which results $(V_{GS} - V_t)=0.5\text{V}$ OR $V_{GS}=0.5 + 0.7=1.2\text{V}$
- We know $V_{GS}=V_G - V_s$ i.e $1.2 = 0 - 1.2$
- Hence $V_s = -1.2\text{V}$



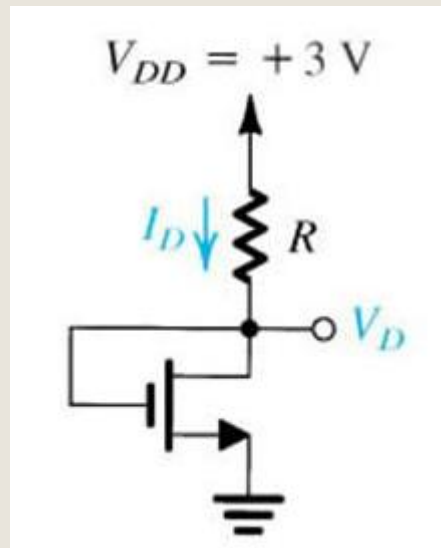
Numerical -2

- $$R_S = \frac{V_S - V_{SS}}{I_D} = \frac{-1.2 - (-2.5)}{0.4} = 3.25\text{K}\Omega$$

Similarly
$$R_D = \frac{V_{DD} - V_D}{I_D} = \frac{2.5 - 0.5}{0.4} = 5\text{K}\Omega$$

Numerical -3

- Design the circuit shown in fig. to obtain a current I_D of $80\mu\text{A}$. Find the value required for R and find dc voltage V_D . Let the NMOS transistor have $V_t=0.6\text{V}$, $\mu_n C_{ox}=200\mu\text{A}/\text{V}^2$, $L=0.8\mu\text{m}$ and $W=4\mu\text{m}$. Neglect the channel length modulation effect.



- Solution:
- From Fig. Drain is connected to gate, hence $V_D = V_G$, hence NMOS is operating in Saturation region.

Numerical -3

$$\bullet I_D = \frac{1}{2} u_n C_{ox} \frac{W}{L} (V_{GS} - V_t)^2$$

We can write : $(V_{GS} - V_t) = \sqrt{\frac{2I_D}{u_n C_{ox} \frac{W}{L}}}$

$$(V_{GS} - V_t) = \sqrt{\frac{2 \times 80}{200 \times \frac{4}{0.8}}} = 0.4V$$

$$V_{GS} = 0.4 + 0.6 = 1V$$

Since $V_s = 0V$

Hence $V_D = V_G = 1V$

Hence required value of R

$$R_D = \frac{V_{DD} - V_D}{I_D} = \frac{3 - 1}{0.08} = 25K\Omega$$

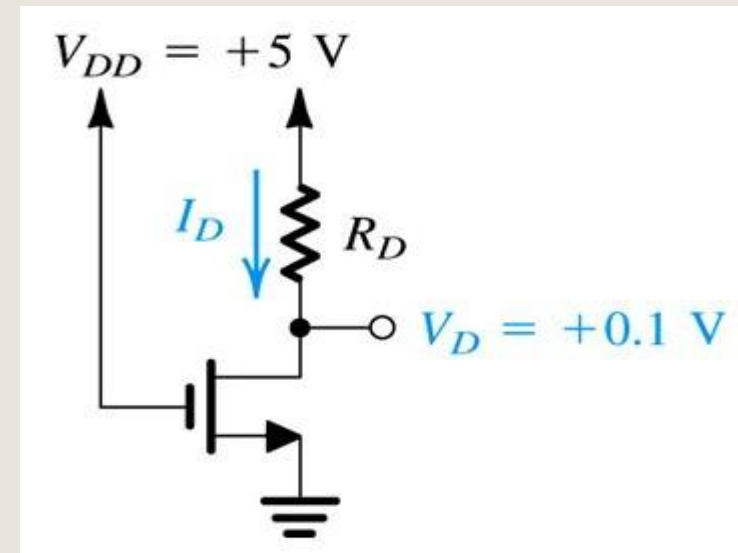
Numerical - HW

- Redesign the circuit in Numerical-3 to double the value of I_D without changing V_D . Give new values for W/L and R .

Answer: $W/L=10$ i.e. $8\mu\text{m}/0.8\mu\text{m}$, $R=12.5\text{K}$

- Design the circuit in fig to establish a drain voltage of 0.1V . What is the effective resistance between drain and source at this operating point?

Assume $V_t=1\text{V}$ and $K_n(W/L)=1\text{mA/V}^2$



Answer: $R_D=12.4\text{K}$, $r_{DS}=253$

Its Quiz Time

<https://forms.gle/vgZLfLnRCvUJXSNMA>